

REMOTE PLASMA SOURCE MA3000C-743BB

MICROWAVE PLASMA COMPONENTS (2 KW / 3 KW / 2450 MHZ)



Features

- Compact Remote Plasma Source (RPS*) designed for the usage at vacuum chambers
- Superior design for photo resist stripping, chamber cleaning, isotropic etching and surface treatment
- Unparallelled cleaning results for process chambers with complex geometry
- Water cooled plasma zone
- Integrated magnetron head unit and launching unit with isolator
- Simple interfacing to any equipment (KF 40 or ISO-K63)

*(RPS: Plasma is only generated and burning in the RPS, only radicals are reaching the process chamber.)

Outline Dimensions (mm)





Specifications

Microwave-Power	3000 W cw max.	Cooling water	≥ 4 (1,06) I/min (US.gal/min), ≤ 4 (58,02) bar
Frequency	2450 MHz ± 20 MHz		(psi) @ 20 - 25 (68 - 77) °C (°F)
Magnetron	3000 W @ 2450 MHz	Connection magnetron unit	Stäubli (CBI 06.7151/IA/JV)
Applicator alignment	180 °	Connection	Stäubli (CBI 06.1151/IA)
Prim. power circuit	-5100 DC / 0,84 A	plasma source	· · ·
Connection	Lemosa (ERA.3Y.415.CA)	Discharge tube	Ceramic
Reactor outlet connector KF 40		Dimensions	Compact design
Primary control circuit	24 V / DC / 0,2 A		Height: 365 (14,37) mm (inch) Depth: 670 (26,38) mm (inch)
Connection	Various (RJ45)	Weight	Approximately 20 (47.07) kg (lbc)
Gas connection	Swagelok (SS-4-VCR-1-2RS)	weight	
Process gases	$\rm O_{2'}N_{2'}H_{2'}F_{2'}$ Ar, $\rm NH_{3'}CF_4$ and other Fluorine based gases	Conditions	5 °C (41 °F) – 45 °C (113 °F) non-condensing T max. = 45 °C (113 °F) < 3 h / day 80 % to 30 °C (86 °F), above linearly reduced to 50 % at 45 °C (113 °F)
		Prim. heating circuit	230 / 208 V AC / 50 / 60 Hz / 0,38 A
		Connection	Phoenix Contact (1605520)
		Operating pressure	0.2 - 2 torr (maximum 5 torr)

Recommended system components

• Microwave power supply e.g. MX3000D-174KL